EAST Search History

EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S183	8512	(118/52,612,500,319-320,50,326,66).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2010/06/21 13:58
S184	3513	(414/331.04,416.03,416.08,937,940,223.01,749.1,719,217).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2010/06/21 13:58
S185	1713	(427/240).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2010/06/21 13:58
S186	784	(396/611,627).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2010/06/21 14:44
S189	666	S183 and control$4 same (wafer or substrate) same tim$3	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2010/06/21 14:51
S190	53	S189 and reduc$3 near5 process$3 near5 time	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2010/06/21 14:52
S191	70	S183 and control$4 near5 movement$1 near5 (wafer or substrate)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2010/06/21 14:53
S192	119	S184 and control$4 near5 movement$1 near5 (wafer or substrate)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2010/06/21 14:53
S193	21	S185 and control$4 near5 movement$1 near5 (wafer or substrate)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2010/06/21 14:53
S194	12	S186 and control$4 near5 movement$1 near5 (wafer or substrate)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2010/06/21 14:53
S197	8	S192 and reduc$3 near5 process$3 near5 time	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2010/06/21 14:55
S198	322	S183 and heat$3 same develop$3 same coat$3	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2010/06/21 14:56

S199	136	S198 and control$4 same (wafer or substrate) same tim$3	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2010/06/21 14:57
S200	136	S189 and coat$3 same develop$3 same heat$3	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2010/06/21 15:26
S201	19	S200 and reduc$3 near5 process$3 near5 time	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2010/06/21 15:26
S202	1081	(396/604,611,627).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2010/06/21 15:48
S203	214	S202 and control$4 same (wafer or substrate) same tim$3	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2010/06/21 15:49

EAST Search History (Interference)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S205	1024	(118/52,612,500,319-320,50,326,66).CCLS.	US-PGPUB	OR	OFF	2010/06/21 15:48
S206	662	(414/331.04,416.03,416.08,937,940,223.01,749.1,719,217).CCLS.	US-PGPUB	OR	OFF	2010/06/21 15:48
S207	476	(427/240).CCLS.	US-PGPUB	OR	OFF	2010/06/21 15:48
S208	138	(396/604,611,627).CCLS.	US-PGPUB	OR	OFF	2010/06/21 15:49
S209	198	S205 and control$4 same (wafer or substrate) same tim$3	US-PGPUB	OR	OFF	2010/06/21 15:50
S210	137	S206 and control$4 same (wafer or substrate) same tim$3	US-PGPUB	OR	OFF	2010/06/21 15:50
S211	115	S207 and control$4 same (wafer or substrate) same tim$3	US-PGPUB	OR	OFF	2010/06/21 15:50
S212	61	S208 and control$4 same (wafer or substrate) same tim$3	US-PGPUB	OR	OFF	2010/06/21 15:50
S214	34	S209 and heat$3 same develop$3 same coat$3	US-PGPUB	OR	OFF	2010/06/21 15:51
S215	5	S210 and heat$3 same develop$3 same coat$3	US-PGPUB	OR	OFF	2010/06/21 15:52
S216	23	S211 and heat$3 same develop$3 same coat$3	US-PGPUB	OR	OFF	2010/06/21 15:52

6/30/10 10:59:38 PM
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